

4~12wafers Fully automatic single wafer cleaner

Model: SA-SWC-48LS

SA-SWC-48LS is suitable for various semiconductor materials and compatible with multiple wafer sizes. The optimized chamber creates a stable working environment and prevents cross-contamination of chemicals. It supports mainstream industrial protocols and system connection. With outstanding adaptability, it meets diverse etching and cleaning demands in semiconductor manufacturing.



Feature

- Accommodate Multiple Sizes
- A Stable Downflow
- Preventing Cross-Contamination of Chemical Agents
- Support GEM/SECS protocols
- Support MES system

Application

- Si/SiC/GaN
- Substrate and Epitaxial Cleaning
- Photoresist Stripping
- Oxide Removal

Specifications:

Parameter	Descriptions
Wafer Size	4&6/6&8/8&12 inches